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(54) Title (EN): EMBOSsing DEVICE AND EMBOSsing METHOD

(54) Title (FR): DISPOSITIF DE GAUFRAGE ET PROCÉDÉ DE GAUFRAGE

(54) Title (JA): エンボス加工装置及びエンボス加工方法

(57) Abstract:

(EN): In this embossing device (10), an embossing roll (20) has a rugged molding part (22) on the outer circumference thereof. A first backup roll (24), together with the embossing roll (20), takes in and pinches a base material (85). First heating parts (60) heat the first backup roll (24). A second backup roll (26), together with the embossing roll (20), takes in and pinches the base material (85). A contact part (30) is disposed in a first range (R1) so as to face the embossing roll (20). The contact part (30) comes into contact with the rear surface of the base material (85).

(FR): Dans ce dispositif de gaufrage (10), un rouleau de gaufrage (20) présente une partie de moulage accidentée (22) sur sa circonférence externe. Un premier rouleau de support (24), conjointement au rouleau de gaufrage (20), saisit et pince un matériau de base (85). De premières parties chauffantes (60) chauffent le premier rouleau de support (24). Un second rouleau de support (26), conjointement au rouleau de gaufrage (20), saisit et pince le matériau de base (85). Une pièce de contact (30) est disposée dans une première plage (R1) afin de faire face au rouleau de gaufrage (20). La pièce de contact (30) entre en contact avec la surface arrière du matériau de base (85).

(JA): エンボス加工装置(10)では、エンボスロール(20)は、凹凸状の成形部(22)を外周に有する。第一バックアップロール(24)は、基材(85)をエンボスロール(20)と共に挟み込む。第一加熱部(60)は、第一バックアップロール(24)を加熱する。第二バックアップロール(26)は、基材(85)をエンボスロール(20)と共に挟み込む。接触部(30)は、第一範囲(R1)にエンボスロール(20)に対向して設けられる。接触部(30)は、基材(85)の裏面に接する。

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